## **Information sheet**

**Tool Name:** Four target E-Beam Evaporator

**System Owner: Mallikarjuna Chary** 

Contact: Email: snchary@iib.ac.in, Mb. No. 9819472649

Material that can be deposited: Aluminium, Titanium, Silver, Palladium

#### **Limitations / Restrictions:**

➤ This tool is categorized as "semi clean PV" tool.

- ➤ Only samples which satisfy the "semi -clean PV" requirement will be allowed on this tool.
- ➤ Outside samples are to be discussed in Si group meeting and then to be processed inside after approval.
- ➤ All the samples processed in it will be considered as Na/K contaminated.

## Samples size:

- > Si (Minimum size: Quarter of 2 "wafer, Maximum size: 4 "wafers).
- Cleaned glass on case-to-case basis.

# **Violation policy:**

- 1. If there is any mishandling of the system by the AU and it is not reported to the SO on time by the user: He/she will be barred from using the system for 3 weeks and he/she has to attend consecutive cleaning sessions plus one day to assist the facility team in their work.
- 2. If one fails to attend 2-3 cleaning sessions consecutively that too with out informing your cleaning partner or SO, one has to attend back to back cleaning sessions for the next two weeks.
- 3. If the logbook entry is missed, it will be reported as violation.

#### **Cleaning Protocol for Four-target e-beam evaporator:**

- 1. Use lint free cloth and IPA only.
- 2. Clean the instrument body, working table with IPA soaked cloth. (To be done carefully).
- 3. After cleaning, keep all the accessories and tools at proper place and keep the system region neat and clean.
- 4. Please take help of cleaners wherever necessary.
- 5. Please take care of the cables and boxes while the cleaner is cleaning the system and the area nearby.